



D. Thin Film Process Technology 분과

2021년 1월 27일(수), 10:45-12:15 / 채널 A

[WA2-D] Thin Film Process I

좌장: 김우희 교수 (한양대학교), 엄태용 박사 (KRICT)

<p>WA2-D-1 10:45-11:00</p>	<p>Comparative Study between Cyclopentadienyl Titanium Trimethoxide and Cyclopentadienyl Titanium Tris(dimethylamide) for Atomic Layer Deposition of Titanium Oxide</p> <p>Hye-Lee Kim, Romel Hidayat, Yeongchan Choi, Jaemin Kim, and Won-Jun Lee <i>Department of Nanotechnology and Advanced Materials Engineering, Sejong University</i></p>
<p>WA2-D-2 11:00-11:15</p>	<p>수소 플라즈마를 이용한 저온($\leq 150\text{ }^{\circ}\text{C}$) 고품질 sputtered SiO_2 박막 형성</p> <p>Taewon Seo, Gilsu Jeon, Hyuk Park, Juyoung Yun, Seongmin Park, Suwon Seong, and Yoonyoung Chung <i>Department of Electrical Engineering, POSTECH</i></p>
<p>WA2-D-3 11:15-11:30</p>	<p>Reaction Mechanism of Atomic Layer Deposition of SiO_2 Using Bis(diethylamino)silane and Ozone</p> <p>Hyeonsu Roh, Hye-Lee Kim, Donggeon Shin, and Won-Jun Lee <i>Department of Nanotechnology and Advanced Materials Engineering, Sejong University</i></p>
<p>WA2-D-4 11:30-11:45</p>	<p>Area-selective Atomic Layer Deposition Assisted by Short-chain Alkanethiols Self-assembled Monolayers</p> <p>Jeongbin Lee, Jinseon Lee, Jeong-Min Lee, Tae Joo Park, and Woo-Hee Kim <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>WA2-D-5 11:45-12:15</p>	<p>[초청] Directional Ionic Transport across the Oxide Interface Enables Low-temperature Epitaxy of Rutile TiO_2</p> <p>Junwoo Son <i>Department of Materials Science and Engineering, POSTECH</i></p>

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